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(12) **United States Design Patent**
Ota

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(54) **COVER FOR A HEATER STAGE OF A PLASMA PROCESSING APPARATUS**

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(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(52) **U.S. Cl.** **D15/138**; D15/199

(58) **Field of Classification Search** D7/586,
D7/587; D8/70, 74; D9/445, 454; D15/133,
D15/144.1, 199; 117/103; 118/723 AN,
118/723 ME; 216/69; 257/E21.252; 427/562,
427/571, 575

See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

D239,437 S *	4/1976	Boduch	D9/445
4,048,845 A *	9/1977	Gilbert	73/45.5
4,122,964 A *	10/1978	Morris	215/260
4,213,537 A *	7/1980	Caccavale	220/215
D265,176 S *	6/1982	Bock	D9/454
4,779,748 A *	10/1988	King	215/256
4,858,590 A *	8/1989	Bailey	126/39 H
D309,109 S *	7/1990	Allen	D9/436
4,978,567 A *	12/1990	Miller	428/157
D315,309 S *	3/1991	Baughman	D9/456
D328,837 S *	8/1992	Marsten et al.	D7/585
D357,385 S *	4/1995	Addison et al.	D7/407
D386,792 S *	11/1997	Miller	D20/21
D399,245 S *	10/1998	Harden	D18/15

6,093,583 A *	7/2000	Mukerji et al.	438/113
6,108,190 A *	8/2000	Nagasaki	361/234
D442,864 S *	5/2001	Davies	D9/454
6,403,933 B1 *	6/2002	Strodtbeck et al.	219/502
7,153,199 B1 *	12/2006	Decker	451/343

FOREIGN PATENT DOCUMENTS

EP	0592017 A2 *	4/1994
JP	D1197395	2/2004
JP	2004-307939	11/2004
KR	30-0411787	4/2006
TW	596249	6/2004
TW	D110109	4/2006
TW	D113217	10/2006

* cited by examiner

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(57) **CLAIM**

The ornamental design for a cover for a heater stage of a plasma processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front view of a cover for a heater stage of a plasma processing apparatus showing my new design:

FIG. 2 is a rear view thereof;

FIG. 3 is a right side view thereof;

FIG. 4 is a top plan view thereof;

FIG. 5 is a sectional view taken along line 5—5 of FIG. 1 thereof;

FIG. 6 is an enlarged view taken along line 6—6 of FIG. 5 thereof; and,

FIG. 7 is a perspective view thereof.

1 Claim, 3 Drawing Sheets

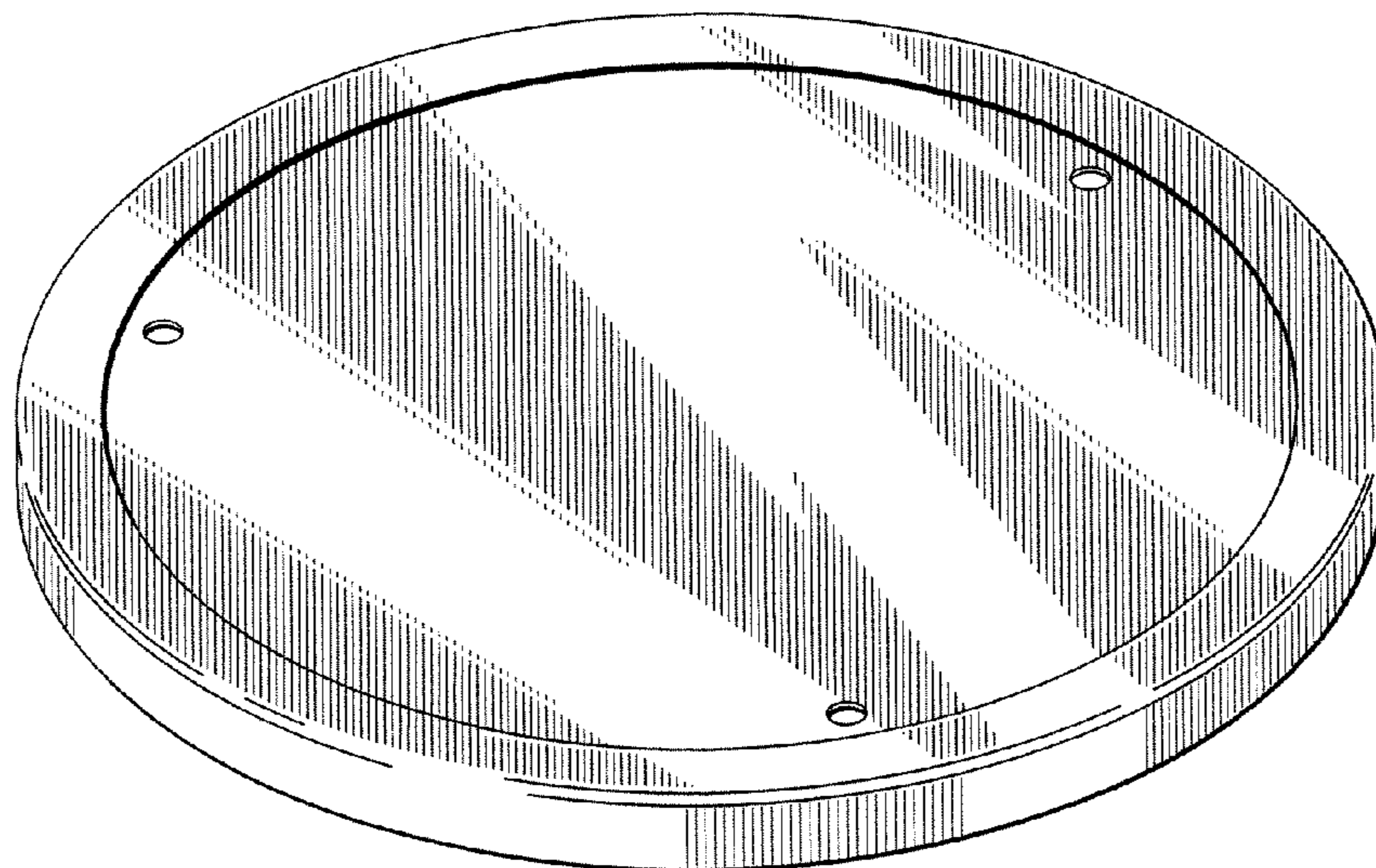


FIG.1

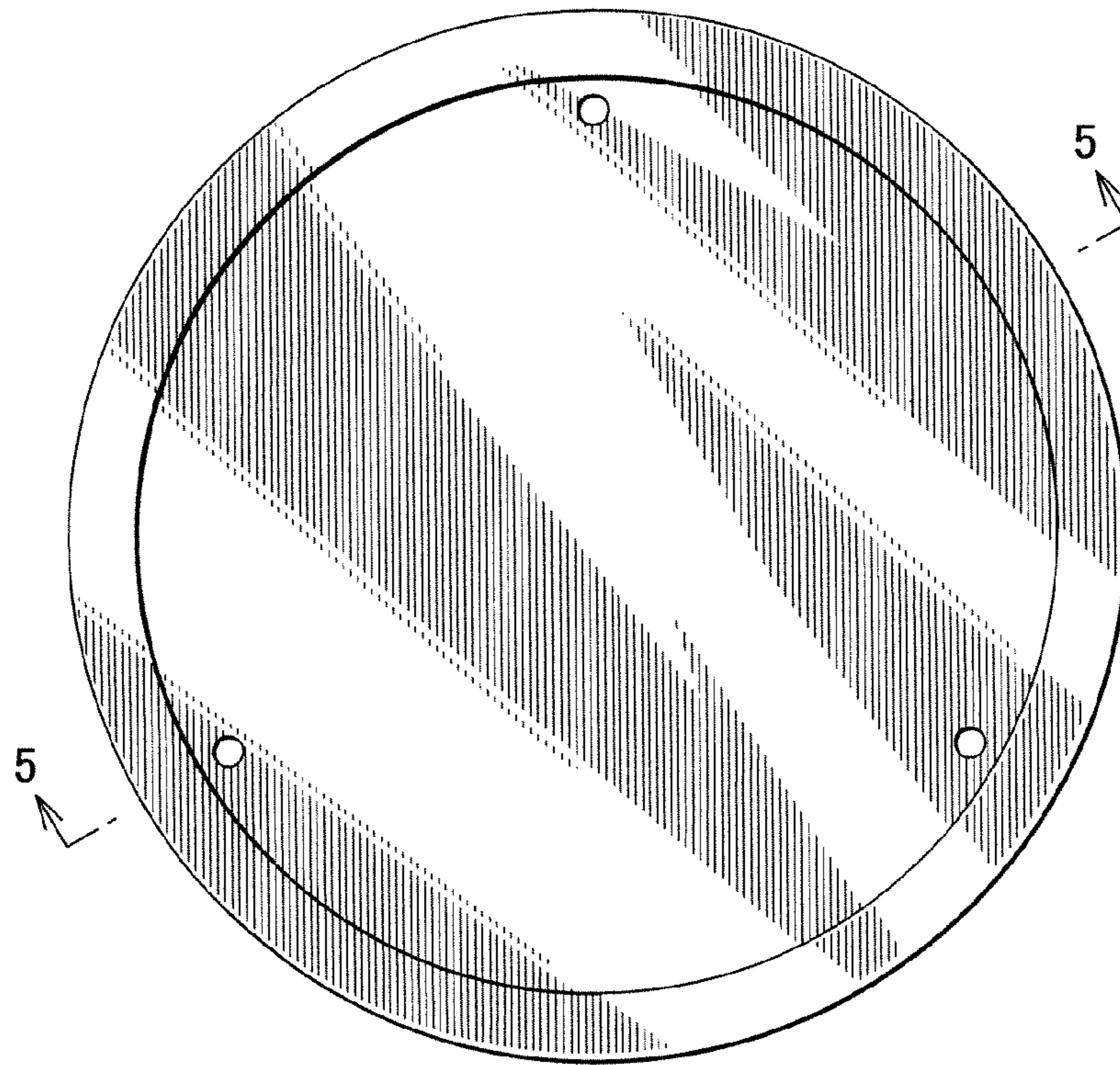


FIG.2

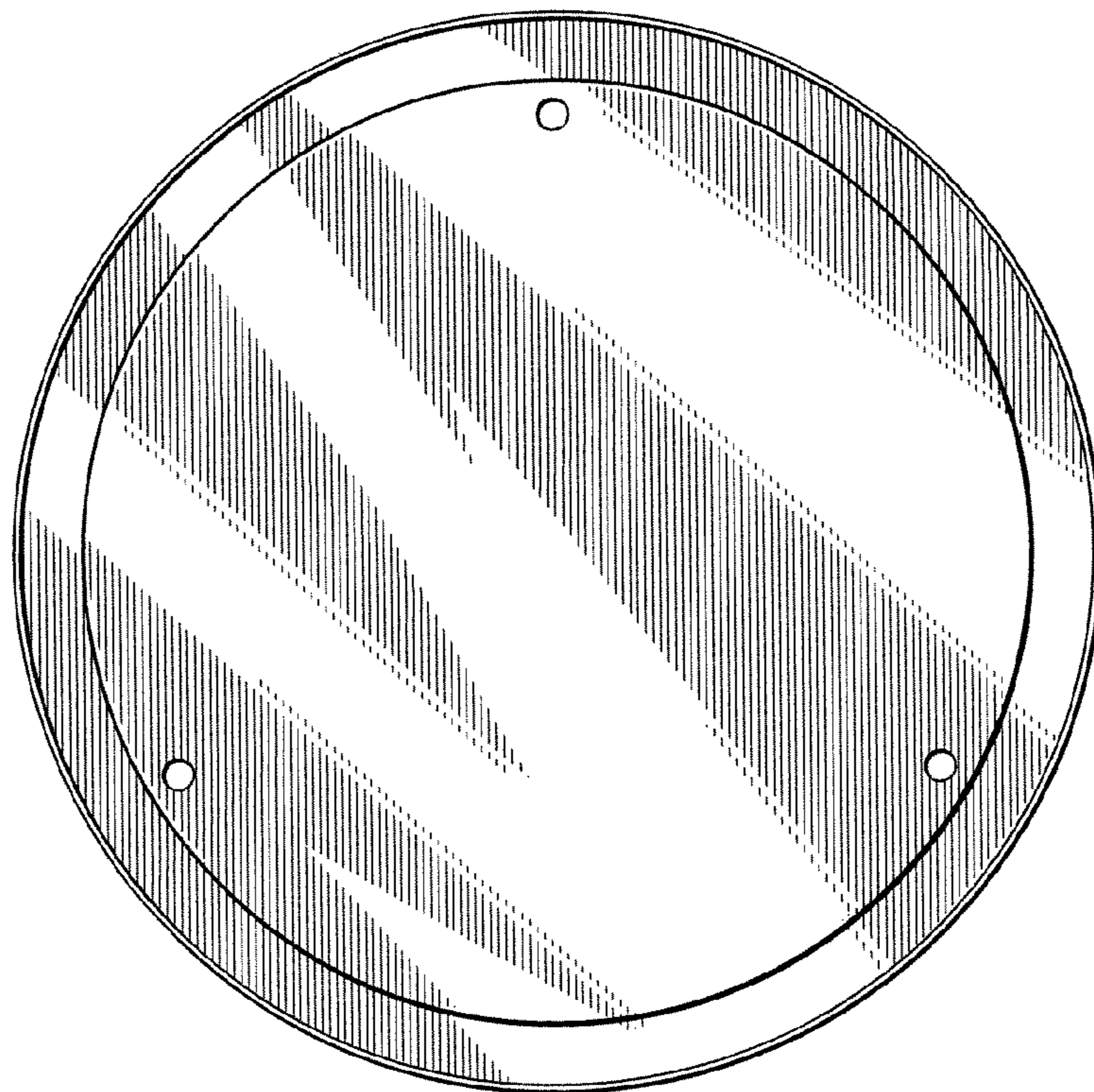


FIG.3



FIG.4



FIG.5

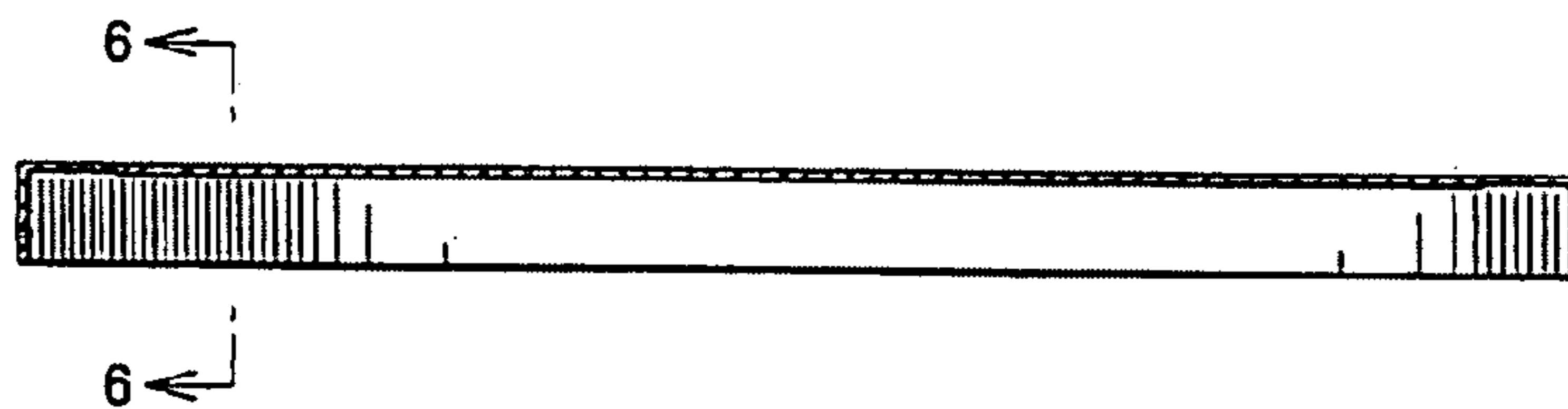


FIG.6

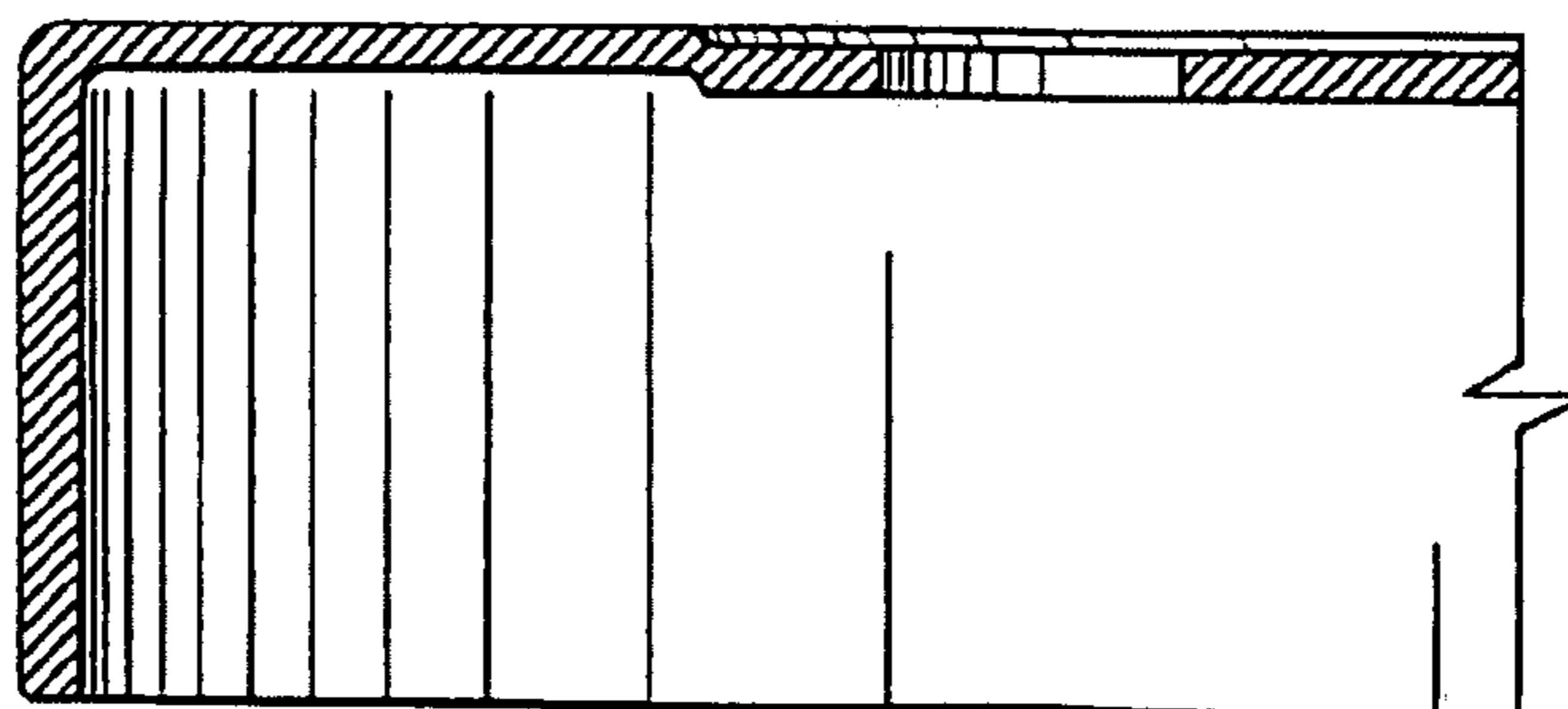


FIG. 7

